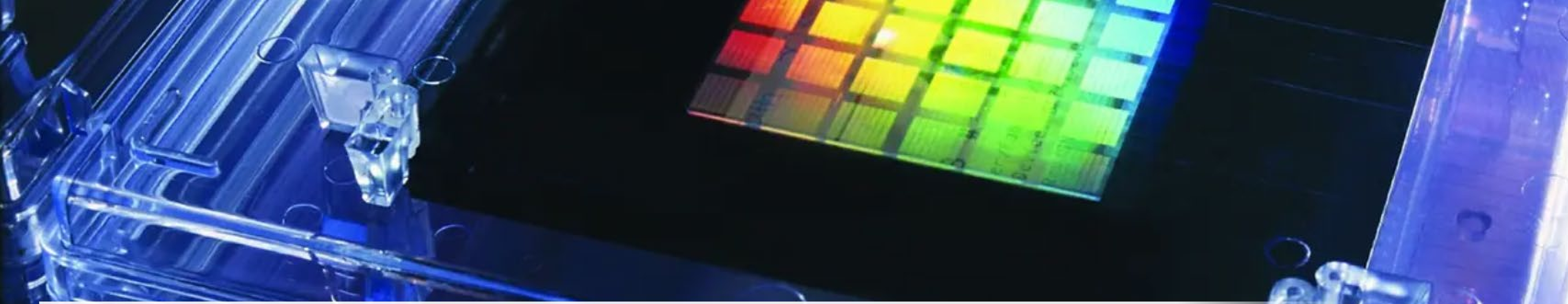
EMLC 2024

The 39th European Mask and Lithography Conference

MINATEC / CEA-Leti, Grenoble, France, June 17-19, 2024

AWARD WINNERS



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ZEISS STUDENT AWARD

ZEISS Award for Talents in Photomask Industry

39th European Mask and Lithography Conference 2024

- Dr. Thomas Scherübl
- ZEISS SMS, Jena

June 19th, 2024

ZEISS Award for Talents in Photomask Industry

The 39th European Mask and Lithography Conference 2024 - EMLC 2024 Grenoble

Self-assembly of shape-complementary DNA origamis for lithography applications

Nicolas Triomphe [1,2], Ludwig Rotsen [1,2], Allan Mills [1], Joséphine Lai-Kee-Him [1], Aurélie Ancelin [1], Guido Rademaker [2], Raluca Tiron [2], Gaëtan Bellot [1]

[1] Centre de Biologie Structurale, INSERM, CNRS, Université de Montpellier,
Montpellier (France)

[2] Univ. Grenoble Alpes, CEA-Leti, Grenoble (France

ZEISS is pleased to honor **outstanding contributions** in the field of photomask technology from students.

The winner will be invited to **SPIE Photomask Technology Conference** in Monterey / CA in October 2024 and receives **prize money** of 2,500 euros.

ZEISS Award for Talents in Photomask Industry

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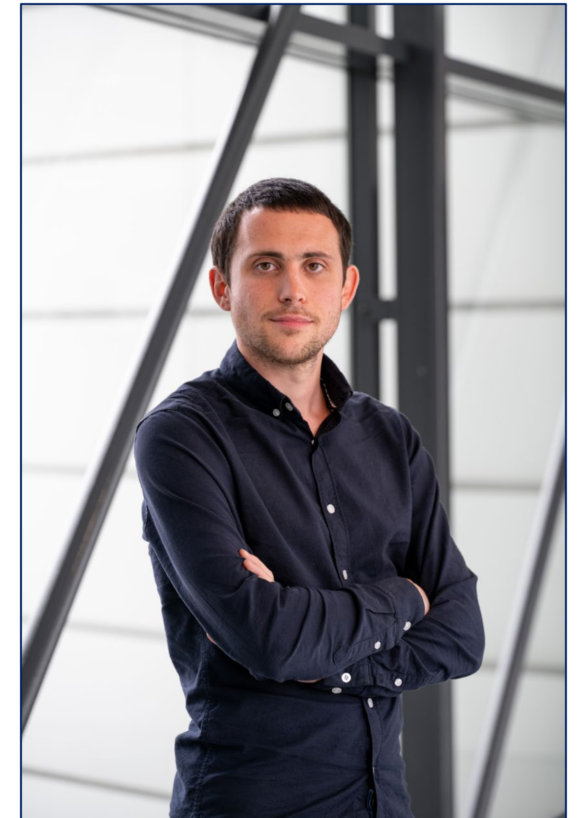

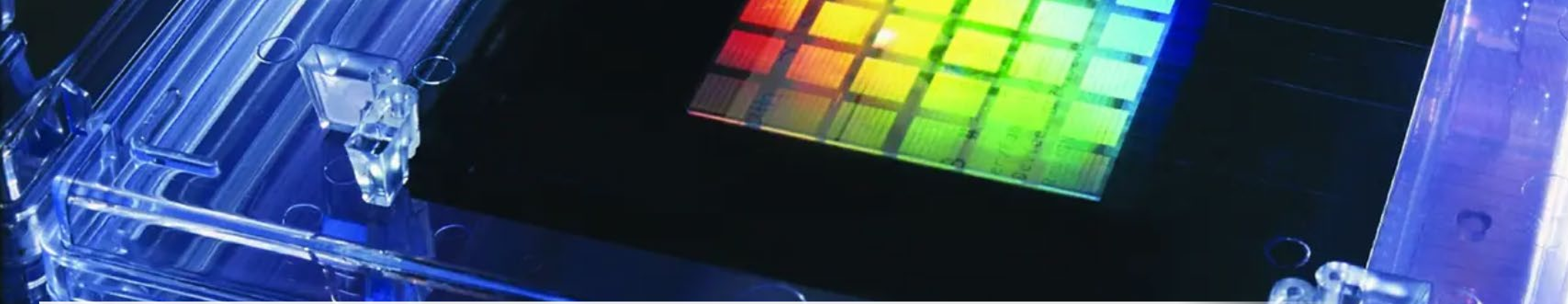

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BEST PAPER AWARD

Stitching at resolution for High NA: an experimental process window study

Lieve Van Look [a],
Vincent Wiaux [a], Natalia Davydova [b],
Guillaume Libeert [a], Tatiana Kovalevich [a],
Nick Pellens [a], Ataklti Weldeslassie [a],
Frank Timmermans [b], Laura Huddleston [b]

[a] imec, Leuven (Belgium)

[b] ASML Netherlands B.V., Veldhoven (The Netherlands)

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BEST POSTER AWARD

Quantitative access to phase-effects in High-NA photomasks using AIMS®

Matthias Roesch,

Grizelda Kersteen, Andreas Verch, Maximilian Albert,

Philip Heringlake, Klaus Gwosch, Renzo Capelli

Carl Zeiss SMT GmbH, Oberkochen (Germany)